

# **SNS COLLEGE OF TECHNOLOGY**



# DEPARTMENT OF ELECTRONICS & COMMUNICATION ENGINEERING

#### 19ECB302-VLSI DESIGN

III YEAR/ V SEMESTER

UNIT 1 -MOS TRANSISTOR PRINCIPLE

TOPIC 4 – MOS IV CHARACTERISTICS



## **OUTLINE**



- INTRODUCTION
- MOS CAPACITOR
- TERMINAL VOLTAGES
- NMOS CUTOFF
- NMOS LINEAR
- NMOS SATURATION
- I-V CHARACTERISTICS
- CARRIER VELOCITY
- ACTIVITY
- NMOS & PMOS I-V PLOTS
- EXAMPLES
- ASSESSMENT
- SUMMARY



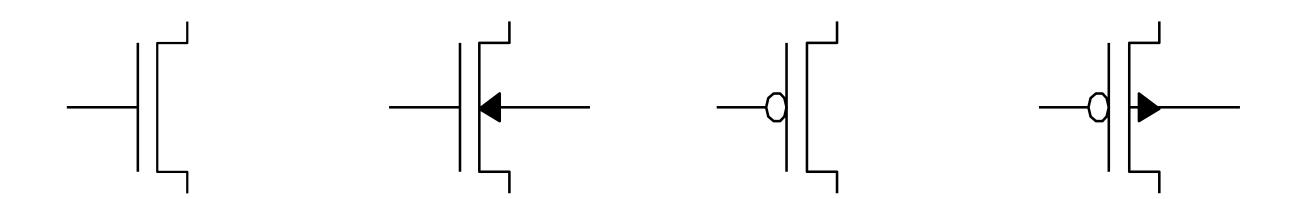
## **INTRODUCTION**



- An ON transistor passes a finite amount of current
  - -Depends on terminal voltages
  - -Derive current-voltage (I-V) relationships
- Transistor gate, şource, drain all have capacitance

$$-I = C (DV/Dt) \rightarrow Dt = (C/I) DV$$

- -Capacitance and current determine speed
- Also explore what a "degraded level" really means

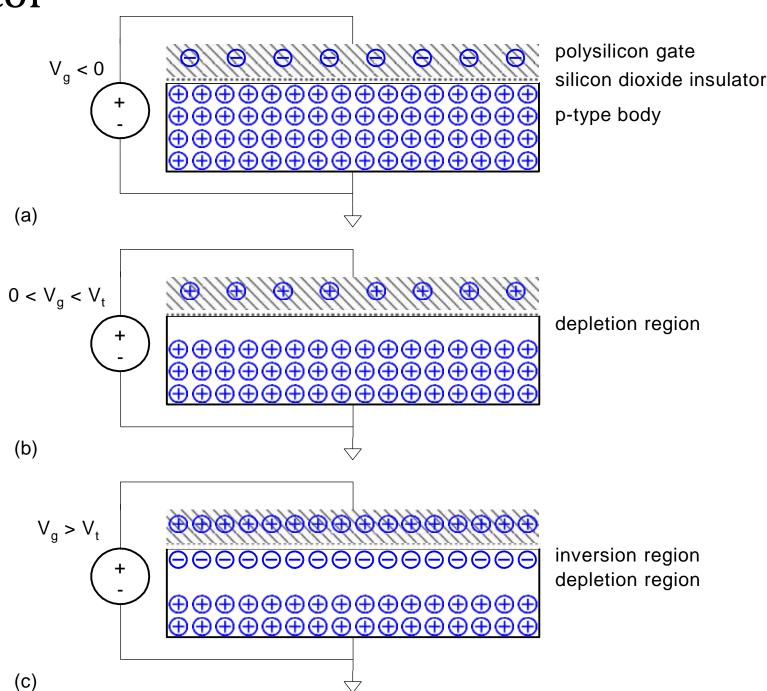




# **MOS CAPACITOR**



- Gate and body form MOS capacitor
- Operating modes
  - -Accumulation
  - –Depletion
  - -Inversion





#### **TERMINAL VOLTAGES**



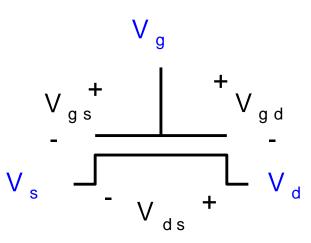
• Mode of operation depends on  $V_g$ ,  $V_d$ ,  $V_s$ 

$$-V_{gs} = V_g - V_s$$

$$-V_{gd} = V_g - V_d$$

$$-V_{ds} = V_d - V_s = V_{gs} - V_{gd}$$

- Source and drain are symmetric diffusion terminals
  - –By convention, source is terminal at lower voltage ,Hence  $V_{ds} \ge 0$
- nMOS body is grounded. First assume source is 0 too.
- Three regions of operation
  - -Cutoff
  - -Linear
  - -Saturation

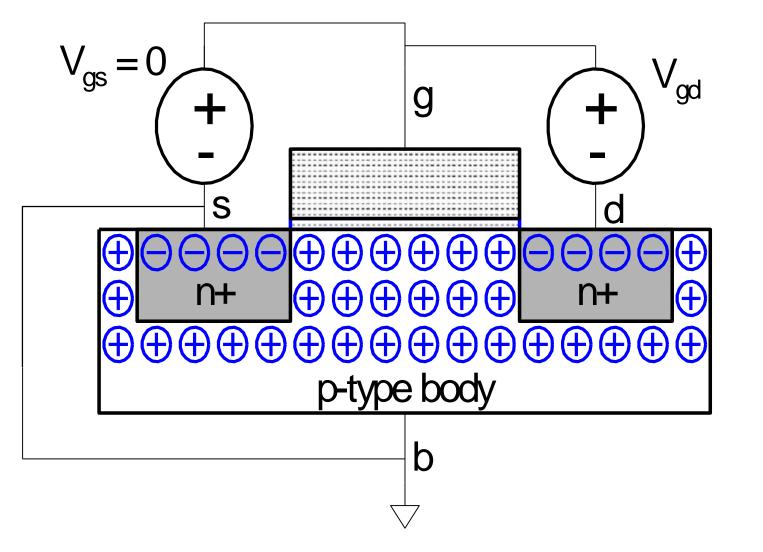




# **NMOS CUTOFF**



- No channel
- $I_{ds} = 0$

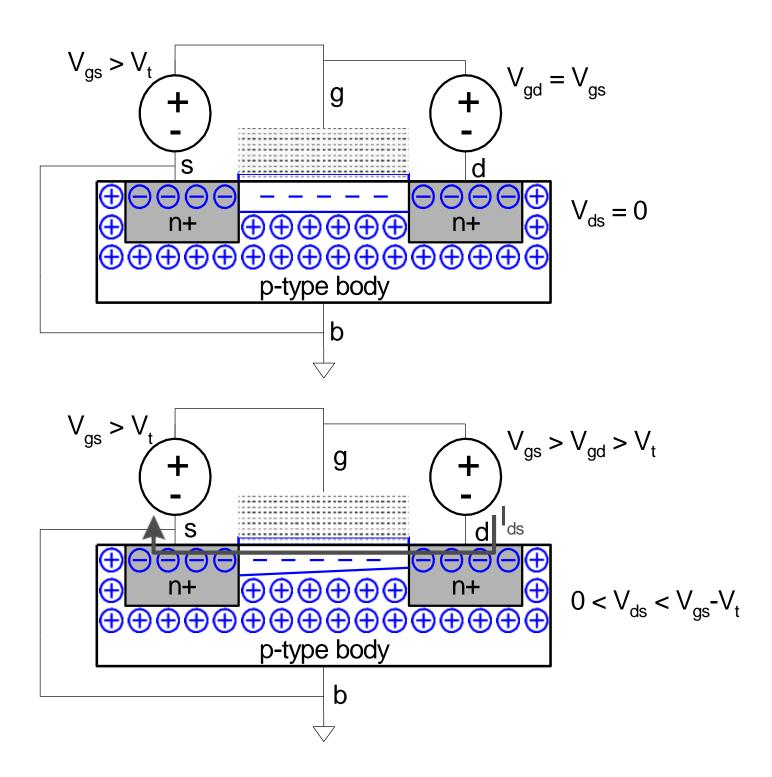




# **NMOS LINEAR**



- Channel forms
- Current flows from d to s
   -e<sup>-</sup> from s to d
- $I_{ds}$  increases with  $V_{ds}$
- Similar to linear resistor

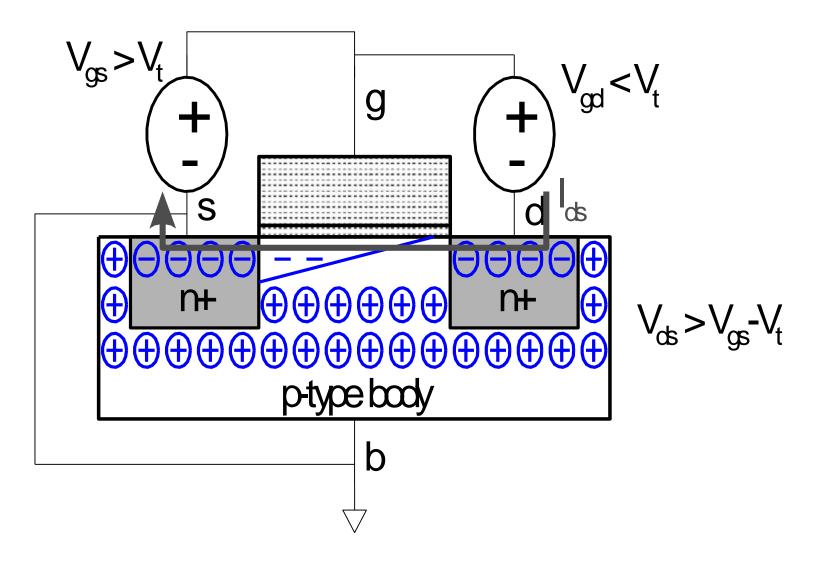




# **NMOS SATURATION**



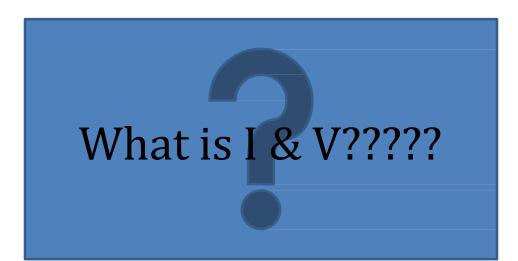
- Channel pinches off
- $I_{ds}$  independent of  $V_{ds}$
- We say current saturates
- Similar to current source





# I-V CHARACTERISTICS





In Linear region,  $I_{ds}$  depends on How much charge is in the channel? How fast is the charge moving?

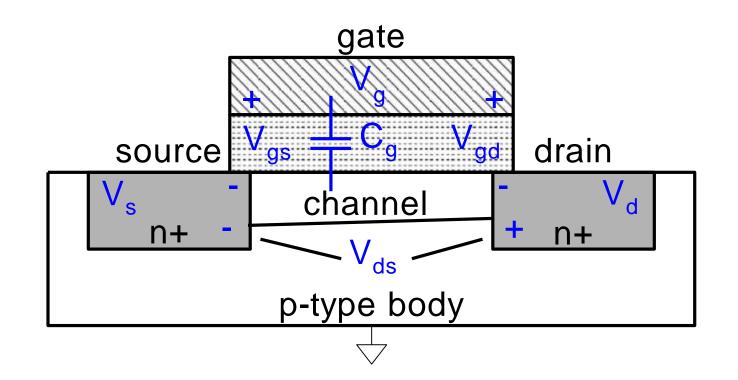


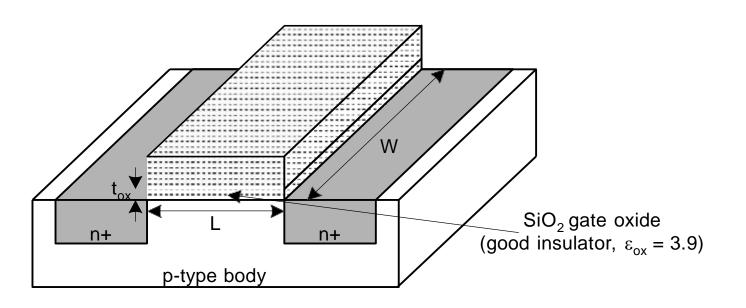
#### **CHANNEL CHARGE**



 MOS structure looks like parallel plate capacitor while operating in inversion

- $Q_{channel} = CV$
- $C = C_g = e_{ox}WL/t_{ox} = C_{ox}WL$
- $V = V_{gc} V_t = (V_{gs} V_{ds}/2) V_t$





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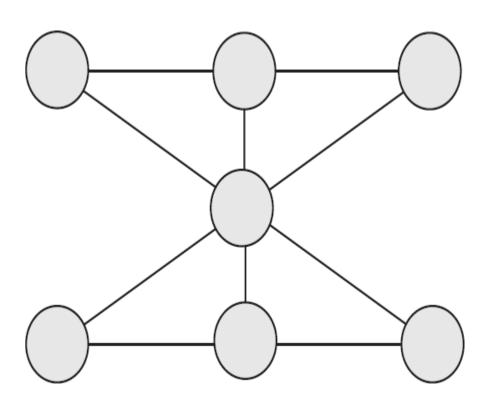
### **CARRIER VELOCITY & ACTIVITY**



- Charge is carried by e-
- Carrier velocity v proportional to lateral E-field between source and drain
- v = mE m called mobility
- $E = V_{ds}/L$
- Time for carrier to cross channel:

$$-t = L / v$$

•Can you put the numbers 1 to 7 In the circles so that every line adds up to 12? You can use each number only once.





### **NMOS LINEAR I-V**



- Now we know
  - –How much charge  $Q_{channel}$  is in the channel
  - -How much time *t* each carrier takes to cross

$$I_{ds} = \frac{Q_{\text{channel}}}{t}$$

$$= \mu C_{\text{ox}} \frac{W}{L} \left( |V_{gs} - V_t - V_{ds}|_2 \right) |V_{ds}|$$

$$= \beta \left( |V_{gs} - V_t - V_{ds}|_2 \right) V_{ds}$$

$$\beta = \mu C_{\text{ox}} \frac{W}{L}$$



#### **NMOS SATURATION I-V**

#### **PMOS I-V**



• If  $V_{gd} < V_t$ , channel pinches off near drain

-When 
$$V_{ds} > V_{dsat} = V_{gs} - V_{t}$$

Now drain voltage no longer increases current

- All dopings and voltages are inverted for pMOS
- Mobility m<sub>p</sub> is determined by holes
  - -Typically 2-3x lower than that of electrons m<sub>n</sub>
  - -120 cm<sup>2</sup>/V\*s in AMI 0.6 mm process
- Thus pMOS must be wider to provide same current
  - -In this class, assume  $m_n / m_p = 2$



#### **NMOS I-V SUMMARY**



Shockley 1<sup>st</sup> order transistor models

$$I_{ds} = \begin{cases} 0 & V_{gs} < V_t & \text{cutoff} \\ \beta \left(V_{gs} - V_t - \frac{V_{ds}}{2}\right) V_{ds} & V_{ds} < V_{dsat} & \text{linear} \\ \frac{\beta}{2} \left(V_{gs} - V_t\right)^2 & V_{ds} > V_{dsat} & \text{saturation} \end{cases}$$



#### **EXAMPLE**



- We will be using a 0.6 mm process for your project
  - -From AMI Semiconductor

$$-t_{ox} = 100 \text{ Å}$$

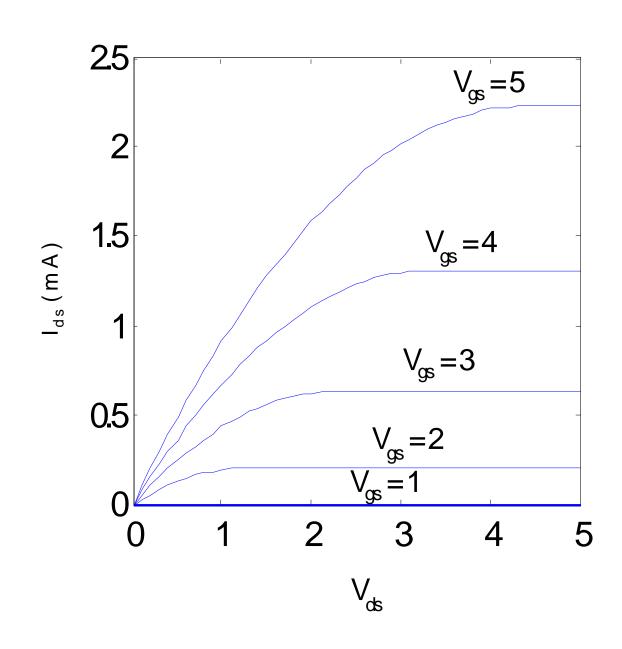
$$- m = 350 \text{ cm}^2/\text{V*s}$$

$$-V_{t} = 0.7 \text{ V}$$

• Plot I<sub>ds</sub> vs. V<sub>ds</sub>

$$-V_{gs} = 0, 1, 2, 3, 4, 5$$

$$-Use W/L = 4/2 l$$



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# **IDEAL NMOS I-V PLOT**

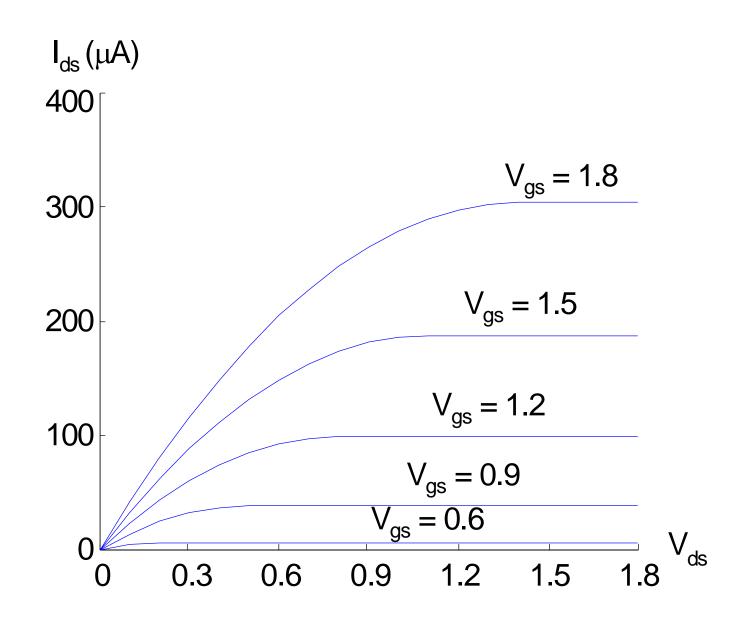


- 180 nm TSMC process
- Ideal Models

$$- b = 155(W/L) mA/V^2$$

$$-V_t = 0.4 V$$

$$-V_{DD} = 1.8 V$$

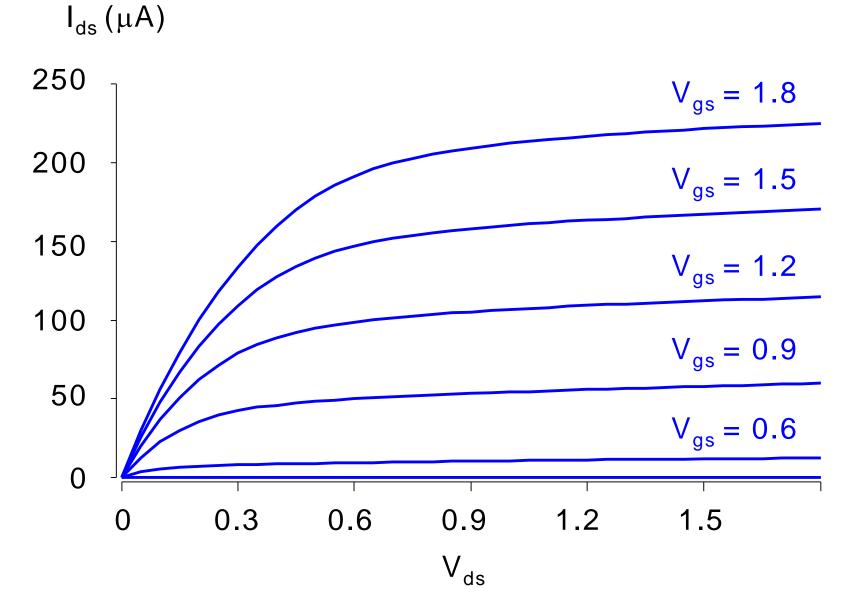


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# SIMULATED NMOS I-V PLOT



- 180 nm TSMC process
- BSIM 3v3 SPICE models
- What differs?
  - ➤ Less ON current
  - ➤ No square law
  - > Current increases
  - > in saturation





#### **ASSESSMENT**



- 1. Compare Accumulation, Depletion, Inversion modes
- $2. Write \ the \ I_{ds} \quad equations \ for \ three \ modes \ in \quad Shockley \ 1^{st} \ order \ transistor \\ models$
- 3.Draw pMOS I-V plot





# **SUMMARY & THANK YOU**